

What is claimed is:

1. A rod target for an arc evaporation source, said rod target employing its outer peripheral surface as an evaporation surface, wherein the opposite ends of said rod target in the longitudinal direction of said rod target are each formed thicker than the central part of said rod target.

2. The rod target for an arc evaporation source according to Claim 1, wherein the length of the thicker portion at each of the opposite ends of said rod target in the longitudinal direction of said rod target is set to be not less than 75 mm nor more than 200 mm.

3. The rod target for an arc evaporation source according to Claim 1, wherein the ratio of the effective consumed sectional area of the thicker portion at each of the opposite ends of said rod target in the longitudinal direction of said rod target with respect to the effective consumed sectional area of the narrower portion in the central part of said rod target is set to be more than 1.0 and not more than 3.0.

4. The rod target for an arc evaporation source according to Claim 1, wherein the boundary portion between the thicker portion at each of the opposite ends of said rod target in the longitudinal direction of said rod target and the narrower portion in the central part of said rod target

is changed in the thickness in a step-by-step manner so that the thickness of said rod target gradually decreases from the thicker portion at each of the opposite ends of said rod target in the longitudinal direction of said rod target toward the narrower portion in the central part of said rod target.

5. The rod target for an arc evaporation source according to Claim 1, wherein a taper portion is provided in the boundary portion between the thicker portion at each of the opposite ends of said rod target in the longitudinal direction of said rod target and the narrower portion in the central part of said rod target so that the diameter of said rod target gradually decreases from each of the thicker portions toward the narrower portion.

6. The rod target for an arc evaporation source according to Claim 5, wherein the tilt angle of the taper portion is set to be not less than 3 degrees nor more than 30 degrees.

7. A method for manufacturing said rod target for an arc evaporation source as recited in Claim 1, comprising integrally assembling the thicker portion at each of the opposite ends of said rod target in the longitudinal direction of said rod target and the narrower portion in the central part of said rod target, after, at least, separately producing the thicker portion at each of the opposite ends

of said rod target in the longitudinal direction of said rod target and the narrower portion in the central part of said rod target.

8. An arc deposition device in which a rod target for an arc evaporation source and work are provided in a vacuum vessel, in which a target material is evaporated from the outer peripheral surface of the rod target for an arc evaporation source, and in which the evaporated target material is caused to adhere to the work, wherein the rod target for an arc evaporation source as recited in Claim 1 is used as the rod target for an arc evaporation source provided in the vacuum vessel.